PETEC Equipment List



| Equipment code | Equipment | Model | Max Substrate size | Additional Details |
|----------------|---------------------------------------|-----------------|----------------------|--|
| O2TAM | Tamarack Proximity Mask Aligner | 152 | 12" Substrate | 4" 6" 8" Square Substrates can be accommodated. |
| 01SUS | Suss Microtec Coating System | 12RC | 9" Square, 12" Round | Chuck Sizes for 4" 6" and 8". |
| O2BRE | Brewer Spin Coater | 200FX | 12" Substrate | Resist Coater |
| 01HOT | Brewer Hot Plate | M10 | 12" Substrate | Nitrogen Purge configured. |
| O3BRE | Brewer Spin Developer | 200FX | 12" Substrate | Spray and Puddle Develop |
| O4BRE | Brewer Spin Etcher | 200FX | 12" Substrate | Au Etch and others can be added. |
| 01DWL | Mask Writer DWL | DWL66FS | 8" Substrate | 4mm&20mm write Heads (1 micron and 5micron resolution) |
| 01LAS | Laser Pro | Sprit GE | | Laser Scribe (not ablation) |
| O1LIT | Litrex | 120L | 370 x 470mm | Inkjet Printer system DPN capability |
| 01MRC | MRC Sputter Tool | MRC 603 | 12" Substrate | Configured to Al, Ti, Au and ITO |
| O1FAS | Wet Etch Bench 1 Acid | FAST_CPI_ACID 1 | 12" Substrate | Au/Ti/Al/ITO Etchants. 2 Heated Baths. With dump rinse |
| 02FAS | Wet Etch Bench 2 Solvent | FAST_CPI_SOL 1 | 12" Substrate | With dump rinse |
| 03FAS | Wet Etch Bench 3 Alkali | FAST_CPI_ALK 1 | 12" Substrate | With dump rinse |
| 01SUN | Plastic to glass Laminator | TMS22SF | 450 x 550mm | Not heated chuck |
| 02LAU | Laurell Spin Processor | WS 400 | 4 " | Manual Dispense |
| O5BRE | Brewer Spin Bake Unit | 100CB | 6" Substrate | Manual Dispense |
| 01PLA | Plasma Lab | 800 Plus | 12" Substrate | RIE/ Plasma Etch |
| 01PLQ | Plasma Quest Thin Film In Line System | ILH 550 | 12" Substrates | Hi rate, low stress Al and ITO Capability |
| 01M3D | Optomec | M3D300CE | 12" Substrates | Aerosol Jet Print (ultrasonic and pneumatic atomiser) |
| O1RKK | RK Rotary Coater | | R2R | Reverse Grauve/ Slot die coating |
| 06BRE | Brewer Spin coater 12" | 200FX | 12" Substrate | Resist Coater, Dual Drain. |
| 02HOT | Brewer Spin CEE M10 | M10 | 12" Substrate | Nitrogen Purge configured. |
| O7BRE | Brewer Spin coater 12" | 200FX | 12" Substrate | Resist Coater, Dual Drain. |

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| O3HOT | Brewer Spin CEE M10 | M10 | 12" Substrate | Nitrogen Purge configured. |
| 01MOR | Moorfield Evaporator | | 4" Substrate | Thermal Evaporation system |
| 02MOR | Moorfield MiniLab system | | up to 8" Substrate | Can be configured as Evap or Sputter system |
| 01SCS | Parylene Coater | Speciality Coating Systems | 6" Substrate | Deposition System |
| 01PE100 | PE100 Etcher | PE100 | | O2 and Ar gas supplied |
| 01MYC | Miyachi Bonder | Emerald 25 | | Bonder (note: not owned by PETEC) |
| O1NAN | Nano-master Glass Cleaner | LSC4000 | 12" Substrate | Brush clean and megasonic |
| O1ORB | Orbotech | FPI-7099M | 370 x 470mm | Defect detection and review on patterned substrates 1-5 um |
| 01HIT | Hitachi SEM | \$3700 | | EDAX enabled, additional ion beam polishing system available (note: this is not a focussed ion beam system) |
| 01DEK | Veeco Dektak Stylus Profiler | DEKTAK 8 | | 0- 1mm 0.1nm resolution |
| 02WEN | Wentworth Semi Auto Prober - Electrical parameter test | 300S | 200mm heated chuck | Linked to Keithley 4200 SCS running ACS |
| 01AFM | Nanoman Atomic Force Microscope | Veeco | | Tapping mode AFM with EFM (SKP) facility |
| 01CCI | Taly-surf Optical Interferometer | CCI 6000 | | 0.1 Angstrom resolution in Z |
| 01FIL | Filmetrics Automatic Thin Film Mapping | F50-300 | 12" | |
| O1NIK | Nikon Optical CD measurement | Nikon L300 | | Line width measurement to 5.0um. Fluorescence filter cubes. DIC. X-polarisers. Auto XY stage. |
| 01LOT | LOT Oriel Contact angle measuring apparatus | CAM200 | 2" substrate | |
| O1KPT | KP Technology Kelvin Probe System | | 1" substrate | |
| 01SOL | Newport Spectra Solar Simulator | ORIEL 93194 | 8" | Class A |
| 01BOT | Bo-test OLED/OPV test system | LIV 091002 | 2" | IVL testing for OPV and OLED devices |

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| O1TAM | Lithography Stepper (COMING 2012) | | 8", 12" and Gen II | Alignment +/-1.0um. |
| 01LACE | SSL development line | | 4", 6", 8" | Integrated Spin and slot die coating in Nitrogen environment, Metal and Organic deposition and Encapsulation |
| 01AUR | Aurion Dry etch | LIV 091002 | 8", 12" and Gen II | Cassette to Cassette two chamber load lock |
| ОЗНОТ | Brewer Spin CEE M10 | M10 | 12" Substrate | Nitrogen Purge configured |
| O1MUE | CD and Overlay | | 8", 12" and Gen II | Auto measurement of CD and over layl to 1.0 um |
| 01SOL | Coat Bake Developer Cluster Tool | | 8", 12" and Gen II | Cassette to cassette Resist coating , developer, EBR Hot and Cool Plates |
| 02SOL | Wet Etch and Cleaning Cluster Tool (COMING 2012) | | 8", 12" and Gen II | Cassette to cassette Spray etch and Clean |
| 01 SCT | Inline Vertical Sputter (COMING 2012) | | 8", 12" and Gen II | 4 targets TBD |
| O1REO | Rheometer | AR1500 | | |
| O1FTI | FTIR | Nicolet IS10 | | ATR (Ge and ZnSe); transmission and reflectance accessories available. |
| P1223 | Roll-to-Roll Sputter Coater | Optilab | Max web width 400mm Max coating width 350mm | Three sputter sources: Single planar, Dual Planar and Dual Rotary. |
| P1209 | MBraun Glovebox | | 4" | Inorganic Thermal Evaporation and Epoxy Encapsulation |
| P1191 | Ellipsometer | Jobin Yvon MM16 | | |
| P1152 | UV/VIS Spectrophotometer | Evolution 600 | | 190-900nm |
| P1146 | UV/VIS/NIR Spectrophotometer | Cary 5000 | | 175-3300nm |





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| P1188 | Particle Guard Protable Surface Particle Counter | PG-01 | | Detection Limit 0.5um |
| | Dole/Teknek Web cleaner | | Upto 400mm web width | |
| | Mocon Aquatran WVTR Measurement Equipment | Aquatran | 100mm x100mm | 3 Modules Measures to 5x10-4g/m2.day |
| 01DSC | TA Instruments Differential Scanning Calorimeter | Q20 | | Ambient to 600°C |
| 01TGA | TA Instruments Thermogravimetric Analyser | Q50 | | Ambient to 700°C |
| 01DIM | Dimatix printer | DMP 2800 | 210 x 325 mm substrate | 10 and 1 pl (picolitre) drop size |